

RESEARCH PARK

New LANL Facility for Coated Conductor Fabrication, Characterization and Applications

Vladimir Matias, Brady Gibbons

Larry Bronisz, Alp Findikoglu, Sascha Kreiskott

Steve Ashworth, Leonardo Civale, Yates Coulter, Jeff Willis



Accelerated Coated Conductor Development via the Research Park Facility

- 1) Scaled-up fabrication
 - Transition to production by industry
 - Longer samples available for analysis and applications
- 2) High-throughput materials experimentation
 - Test bed for new ideas
 - *In-situ* diagnostics
- 3) Increased interaction with partners
 - Co-location of outside partners
 - User facility, training
- 4) Applications testing lab
 - Lab with unique capabilities for evaluating conductors
 - Capability for testing prototype applications



STC Labs at the Research Park

- 4 new labs for Coated Conductor preparation and 3 for applications development
- CC preparation labs with reel-to-reel tape systems

**Pulsed-Laser
Deposition Lab**

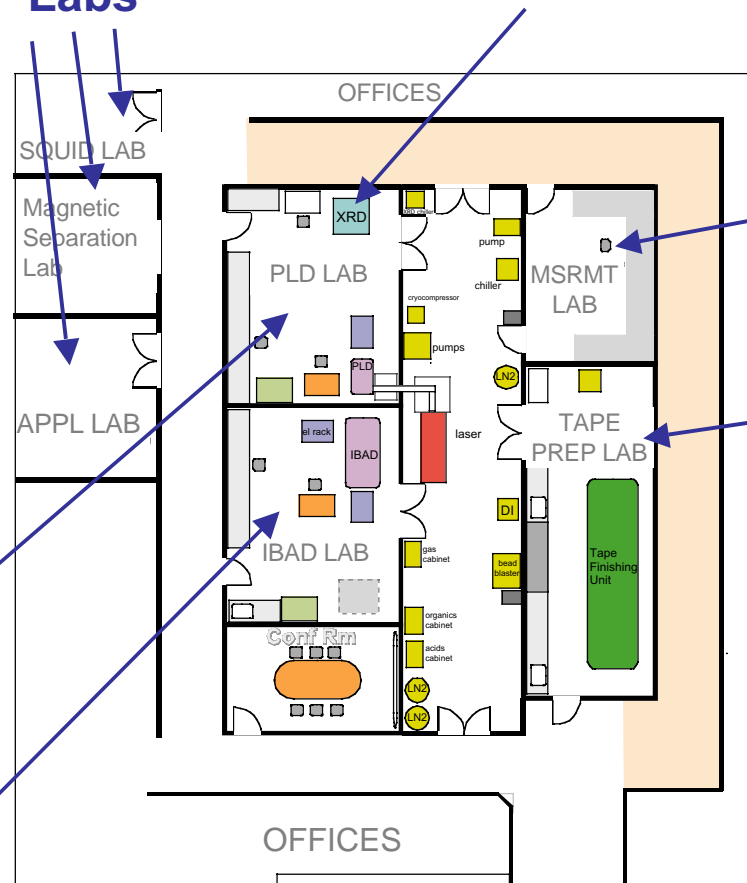
**Ion-Beam Assist
Deposition Lab**

**Applications
Labs**

X-ray Diffraction

**Measurements
Lab**

**Tape Finishing
Lab**



Research Park - June 2001



Research Park - August 2001



Research Park: Oct. 2001 - Feb. 2002



Research Park - July 2002



IBAD Lab



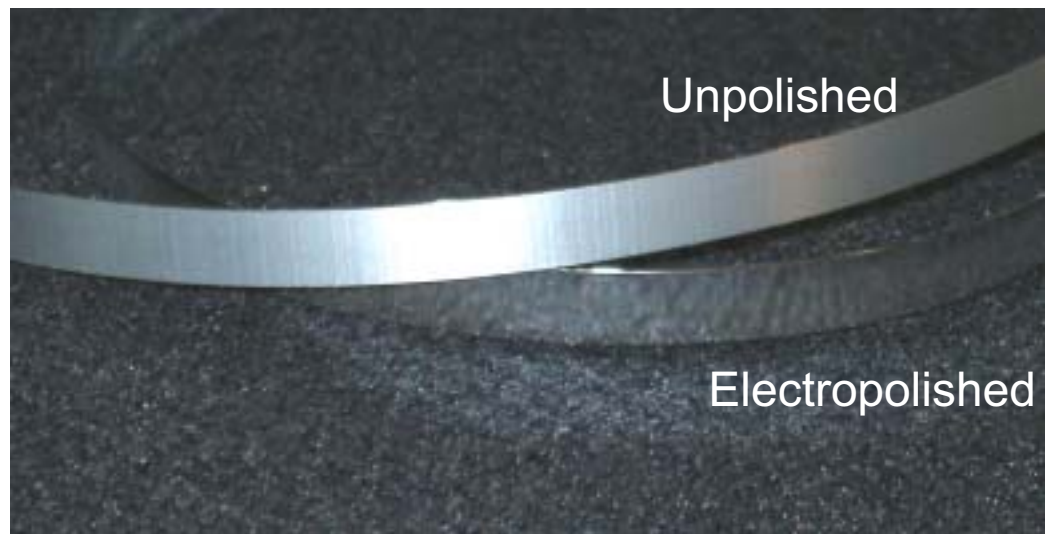
IBAD template tapes on reels

PLD Lab



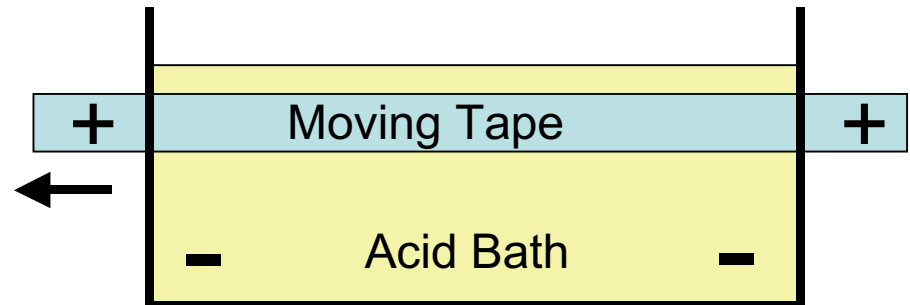
Tape Finishing

- Coated conductors require starting prepared metal tapes with smooth and clean surfaces
- New industrial-type equipment processes reels of metal tape by electropolishing
- Capable of reel-to-reel polishing of tape at high speed up to km lengths
- Capabilities for tape finishing research, including electroplating



Electropolishing cell

- tape speed: 15 - 30 m/hr
- voltage: 5 - 12 V
- current: 5 - 25 A



Results on Surface Smoothing: Optical micrographs

Unpolished Hastelloy C-276

100 μm

RMS roughness from
atomic force micrographs
over 50 μm x 50 μm area

RMS: 40 nm

100 μm

Mechanically polished

RMS: 12 nm

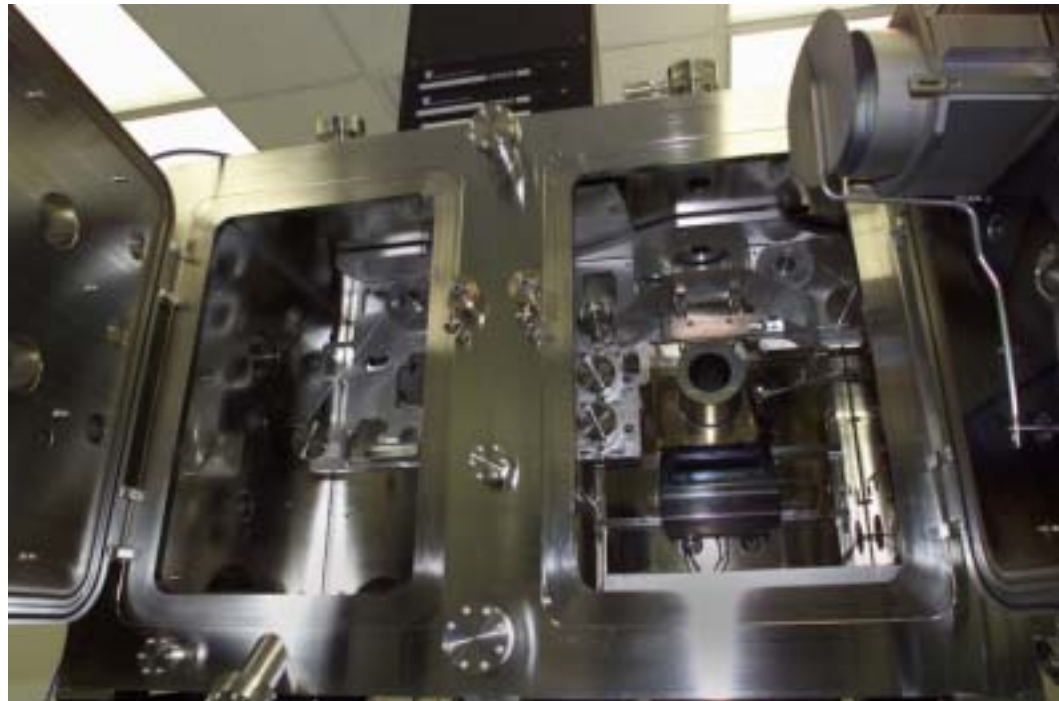
Electropolished

100 μm

RMS: 8 nm

Ion-Beam-Assisted Deposition Chamber

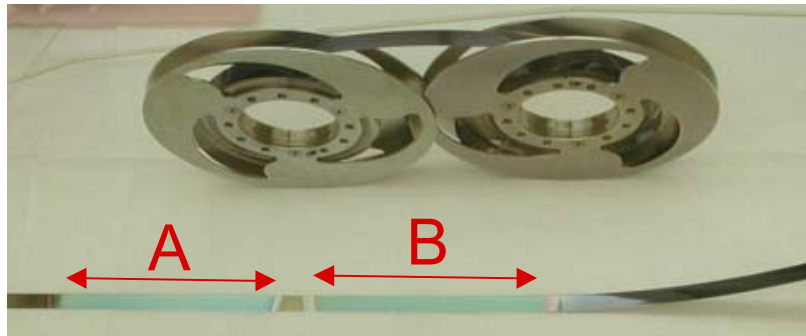
- Large vacuum chamber (6'x4'x3.5')
- Capability for process integration (IBAD and buffer layers)
- Reel-to-reel system provides for tape lengths over 100 meters
- 3000 - 6000 l/s pumping speed: < 2 hrs to pump, vent in 10 minutes: quick turnaround



Sequential Combinatorial Research from Continuous Tape Processing

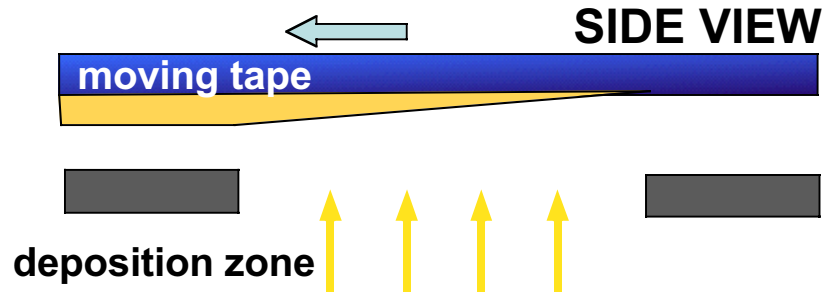
- Continuous tape processing is ideal for exploring process parameters in a sequential way
- We can track positions on tape from one process step to the next and develop a matrix of experiments (either continuously or in stationary batches)

A and B have
different buffer layers
on top of IBAD-MgO



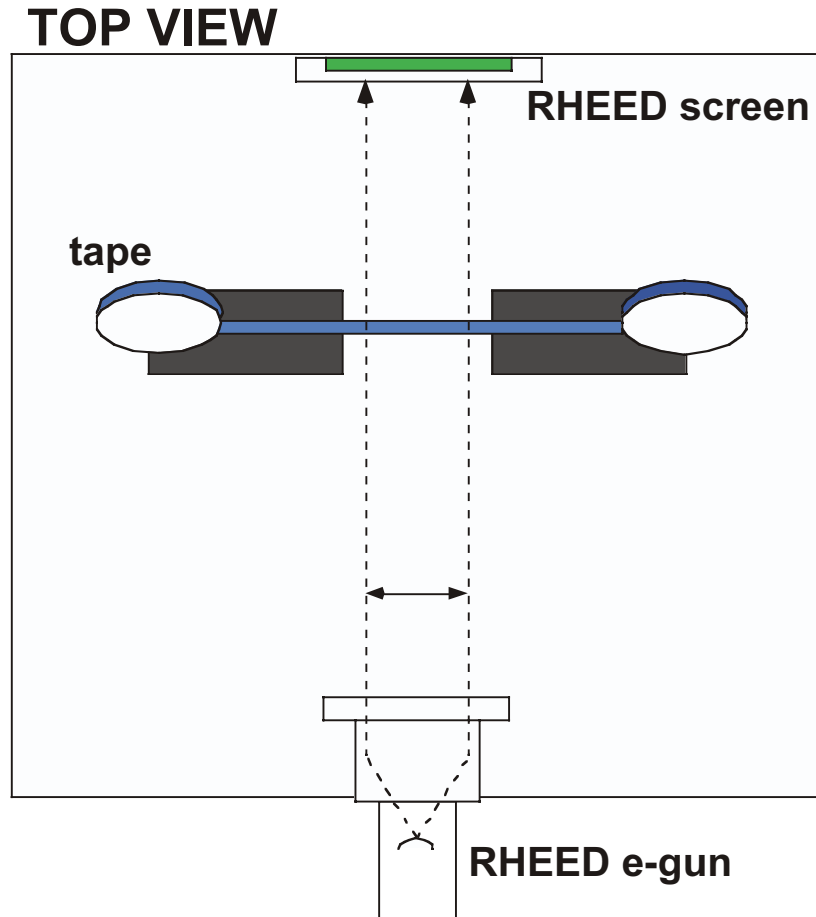
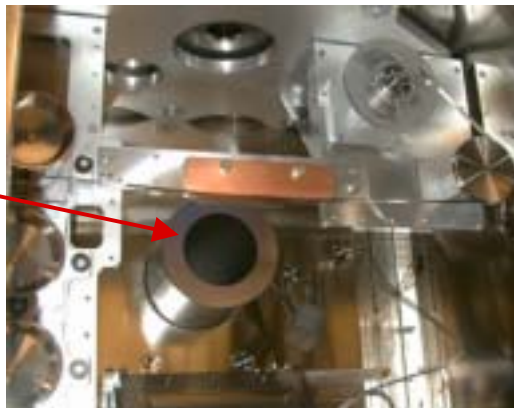
- Such combinatorial research provides for a high-throughput of experiments (100's of experiments in 1 reel) - *in-situ* evaluation
- Currently using this method for optimization of deposition processes
- IBAD process transferred successfully from Paul Arendt's lab to Research Park

Parallel Scanning RHEED for Continuous IBAD

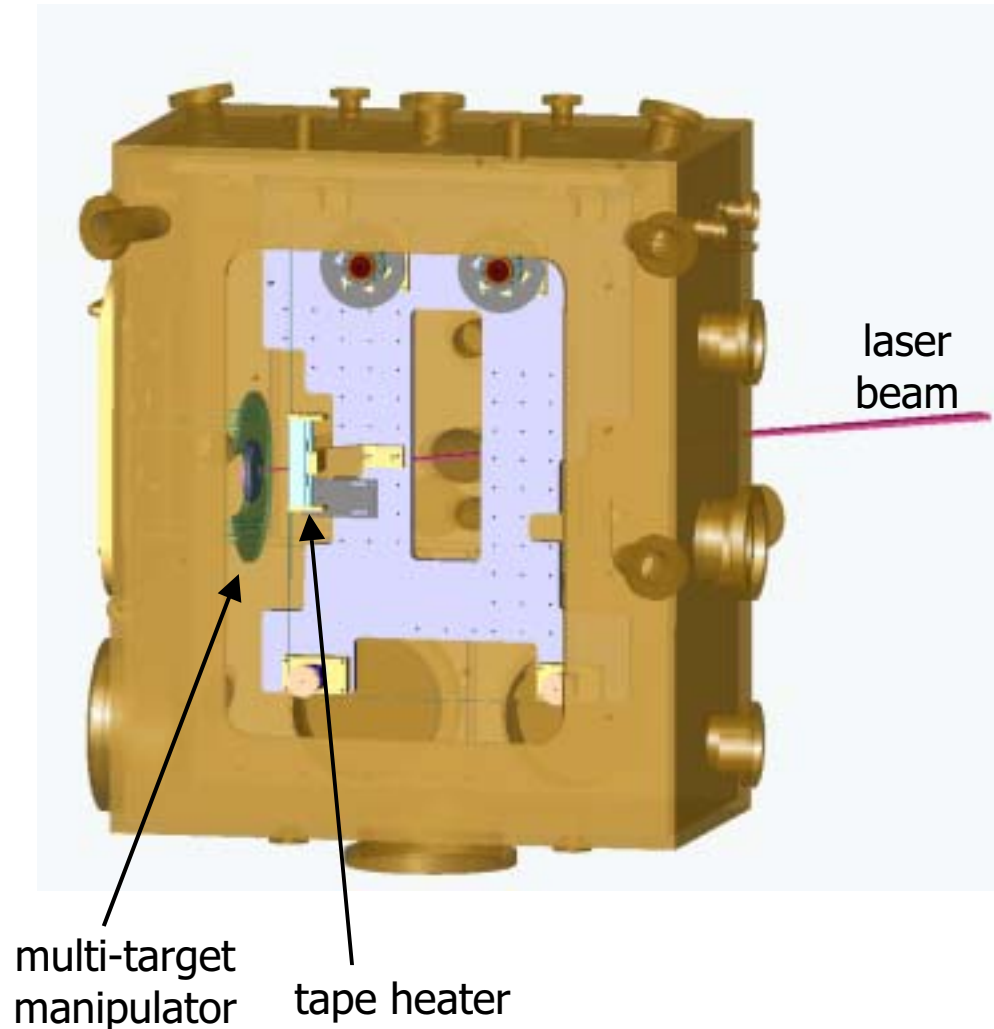


- By scanning the RHEED beam along the tape one obtains RHEED images at different stages of IBAD growth

RHEED gun



Pulsed-Laser Deposition Chamber



- Four 4" targets for deposition of a variety of oxide layers
- Quartz lamp heater allows for heating of tape as it continuously moves through the PLD zone
- *In-situ* adjustment of tape position with respect to laser plume
- Silver deposition integrated

Pulsed-Laser Deposition Chamber

- Relatively large chamber for PLD (4'x3.5'x2')
- Easy access via front and side doors
- 4000 l/s pumping speed, chamber pumps down in 1 hour
- Industrial 200 W XeCl (308 nm) laser is used for PLD

